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(12) **United States Design Patent**
Park

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(54) **NAIL POLISH APPLIQUÉ STRIP**

(71) Applicant: **Park Global Holdings, LLC**, Clifton, NJ (US)

(72) Inventor: **Fa Young Park**, Clifton, NJ (US)

(73) Assignee: **Park Global Holdings, LLC**, Clifton, NJ (US)

(**) Term: **14 Years**

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(51) **LOC (10) Cl.** **28-03**

(52) **U.S. Cl.**
USPC **D28/56**

(58) **Field of Classification Search**
USPC 132/200, 73, 73.5, 285, 74.5; D28/56;
D20/11

See application file for complete search history.

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Primary Examiner — Jennifer Rivard

(74) *Attorney, Agent, or Firm* — John H. Choi

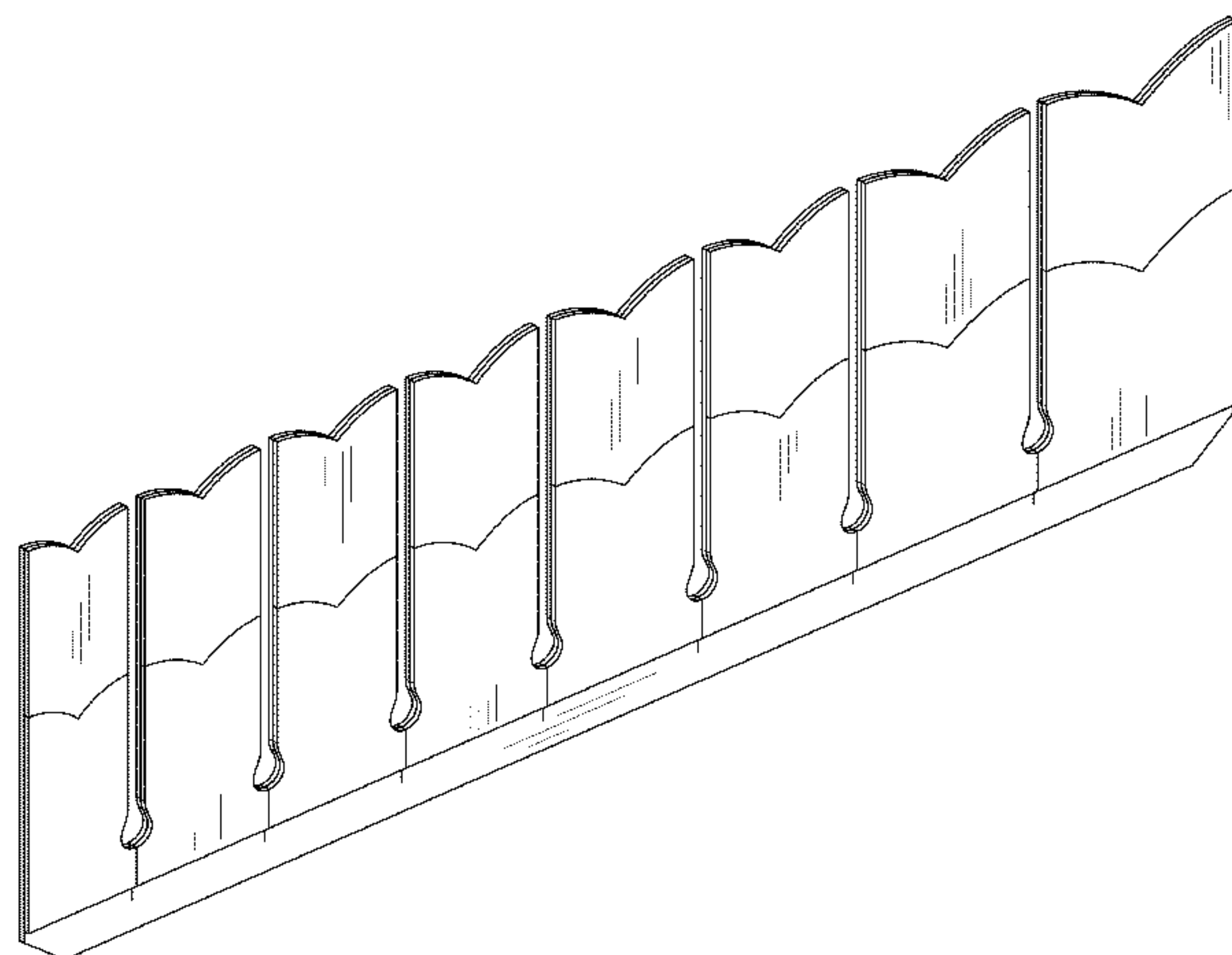
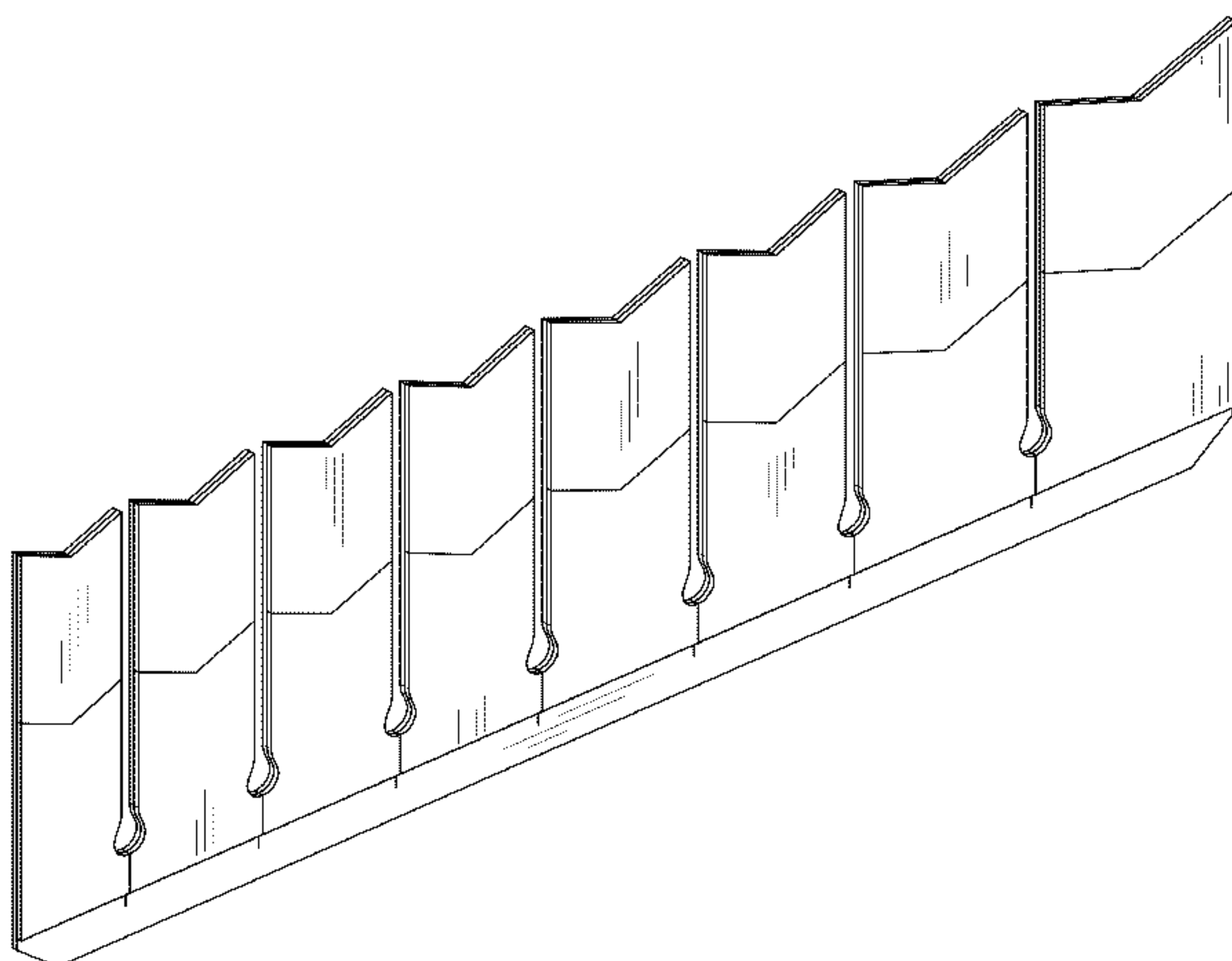
(57) **CLAIM**

The ornamental design for a nail polish appliqué strip, as shown.

DESCRIPTION

FIG. 1 is a perspective view of a nail polish appliqué strip showing a first embodiment of my new design;
 FIG. 2 is a front elevational view of the nail polish appliqué strip shown in FIG. 1;
 FIG. 3 is a rear elevational view of the nail polish appliqué strip shown in FIG. 1;
 FIG. 4 is a right side elevational view of the nail polish appliqué strip shown in FIG. 1;
 FIG. 5 is a left side elevational view of the nail polish appliqué strip shown in FIG. 1;
 FIG. 6 is a top plan view of the nail polish appliqué strip shown in FIG. 1;
 FIG. 7 is a bottom plan view of the nail polish appliqué strip shown in FIG. 1;
 FIG. 8 is a perspective view of a nail polish appliqué strip showing a second embodiment of my new design;
 FIG. 9 is a front elevational view of the nail polish appliqué strip shown in FIG. 8;
 FIG. 10 is a rear elevational view of the nail polish appliqué strip shown in FIG. 8;
 FIG. 11 is a right side elevational view of the nail polish appliqué strip shown in FIG. 8;
 FIG. 12 is a left side elevational view of the appliqué strip shown in FIG. 8;
 FIG. 13 is a top plan view of the nail polish appliqué strip shown in FIG. 8; and,
 FIG. 14 is a bottom plan view of the nail polish appliqué strip shown in FIG. 8.

1 Claim, 6 Drawing Sheets



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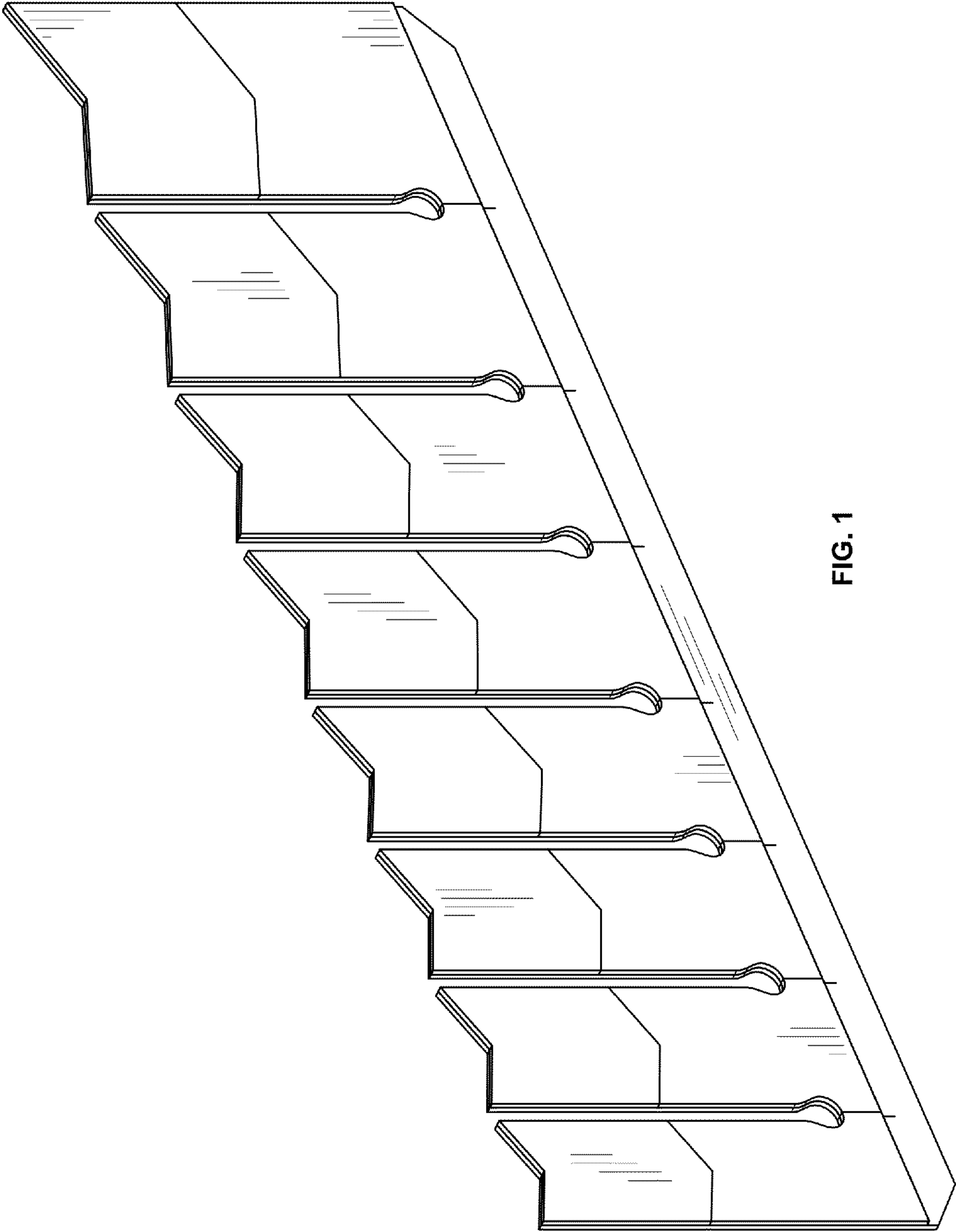


FIG. 1

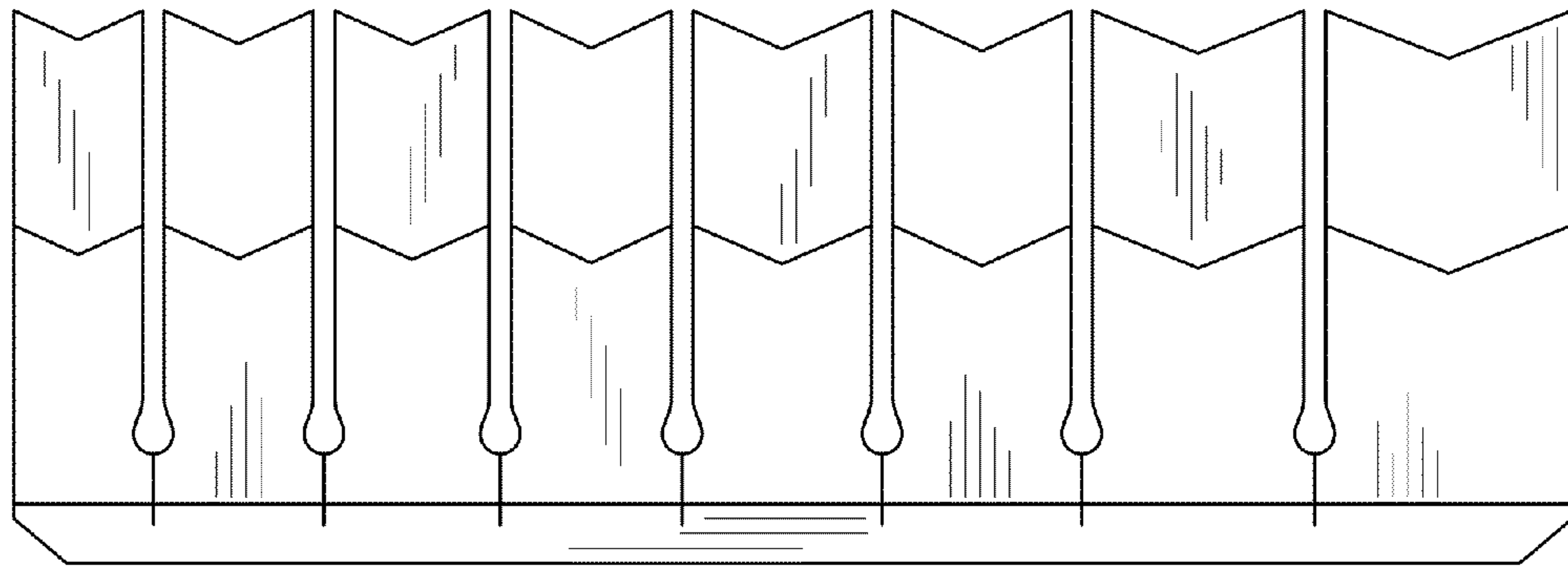


FIG. 2

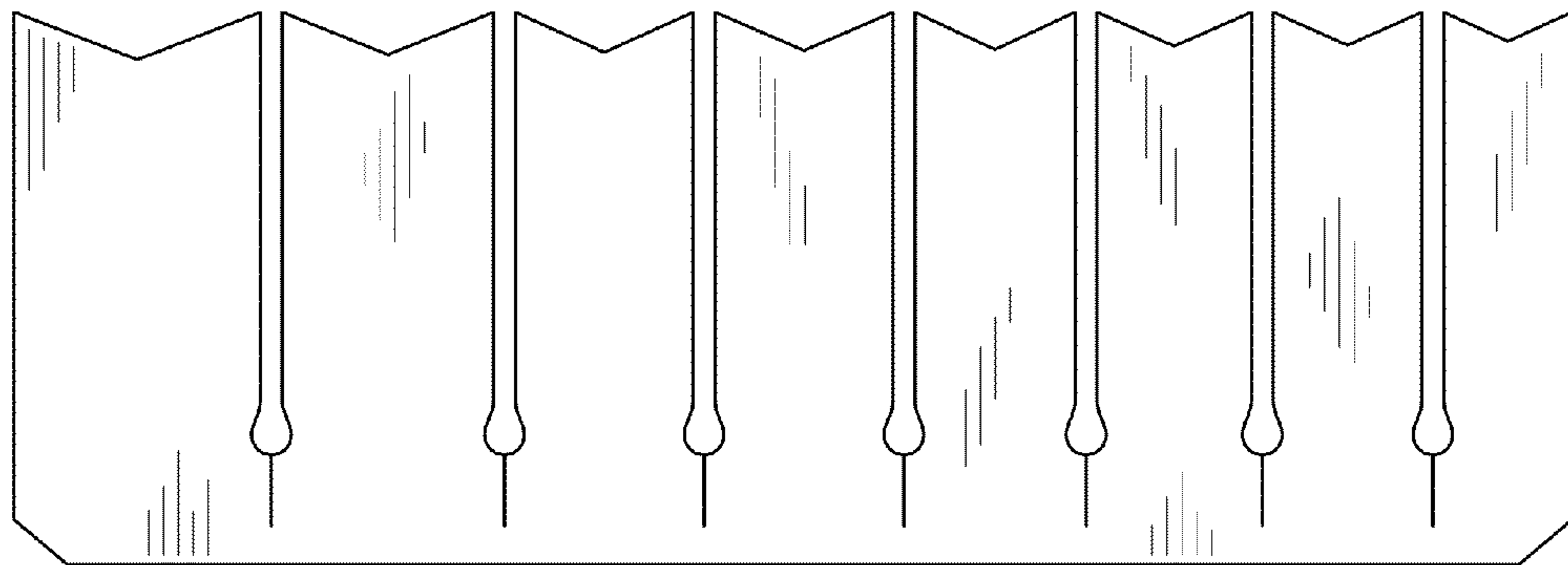


FIG. 3



FIG. 4



FIG. 5

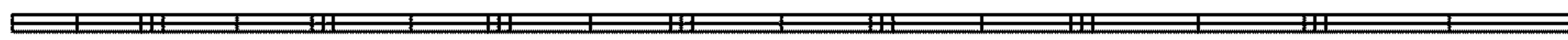


FIG. 6



FIG. 7

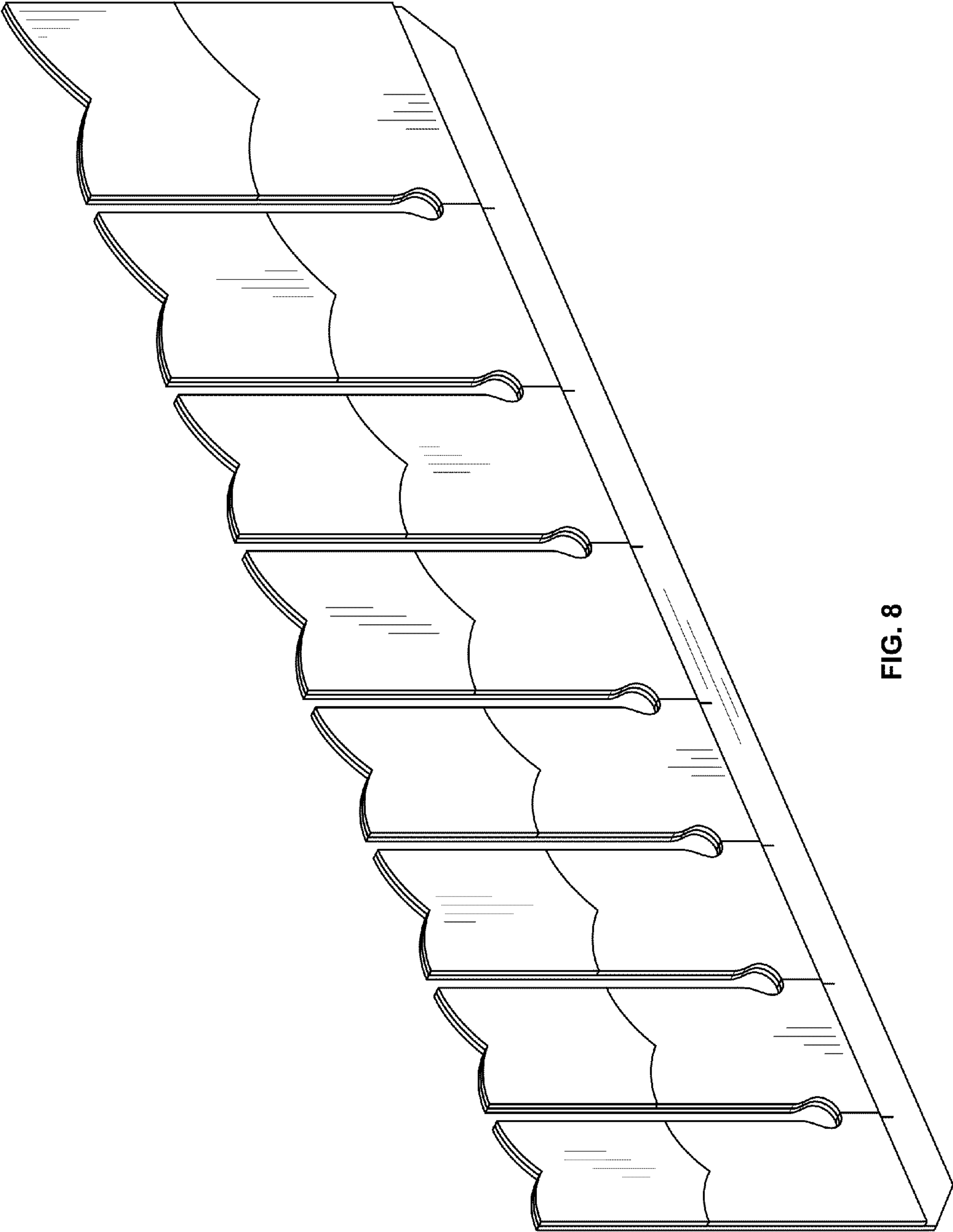


FIG. 8

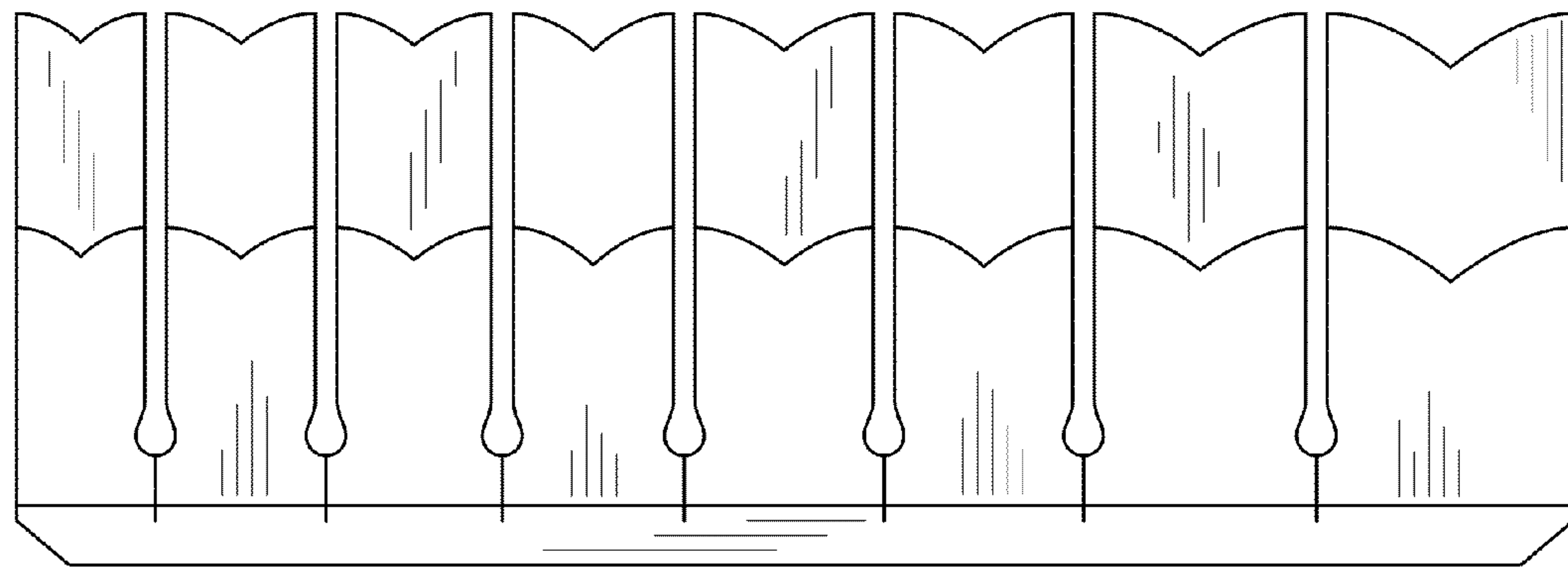


FIG. 9

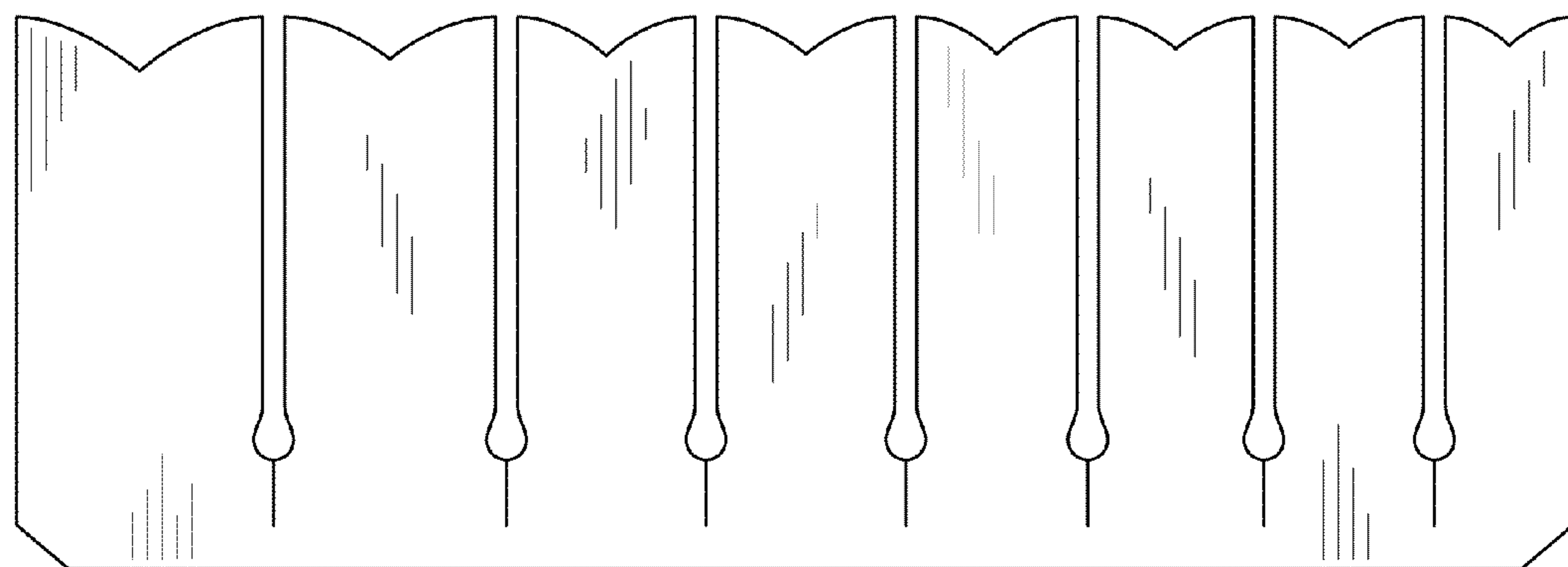


FIG. 10



FIG. 11



FIG. 12

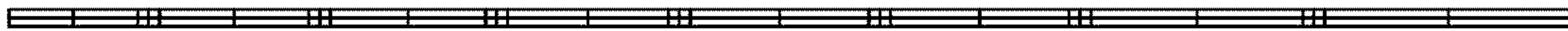


FIG. 13

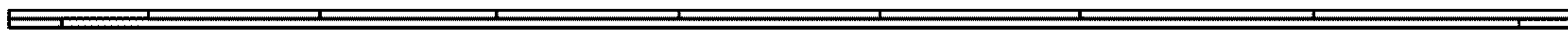


FIG. 14